

# 제23회 한국반도체학술대회

2016년 2월 22일(월)-24일(수), 강원도 하이원리조트

## D. Thin Film Process Technology 분과

Room B

태백II+III(5층)

2016년 2월 23일(화) 10:40-12:40

[TB2-D] Oxide Semiconductors

좌장 : 김형섭(성균관대학교), 조성목(한국전자통신연구원)

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| TB2-D-1 | 10:40-10:55 | <b>Analysis of Channel Quality of Sputtered IGZO Thin Film Transistors using a Conductance Method with a Corrected Contact Resistance</b><br>Manh-Cuong Nguyen <sup>1</sup> , Jae-Won Choi <sup>1</sup> , Soo-Yeun Han <sup>1</sup> , An Hoang-Thuy Nguyen <sup>1</sup> , Sol Kang <sup>1</sup> , Jae Kyeong Jeong <sup>2</sup> , and Rino Choi <sup>1</sup><br><sup>1</sup> Department of Materials Science and Engineering, Inha University,<br><sup>2</sup> Department of Electronic Engineering, Hanyang University |
| TB2-D-2 | 10:55-11:10 | <b>Highly-Stable Memory Operations of Flexible Charge-Trap Memory Thin-Film Transistors using IGZO Channel and ZnO Charge-Trap Layers on Plastic Poly(ethylene naphthalate) Substrate</b><br>So-Jung Kim, Min-Ji Park, Da-Jeong Yun, Won-Ho Lee, and Sung-Min Yoon<br><i>Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University</i>   |
| TB2-D-3 | 11:10-11:25 | <b>High Performance and Stability of Double-gate Type In-Ga-Zn-O Thin Film Transistor on Fully Transparent Glass Substrate</b><br>Min-Ju Ahn and Won-Ju Cho<br><i>Department of Electrical Material Engineering, Kwangwoon University</i>   |
| TB2-D-4 | 11:25-11:40 | <b>Characterizations of p-type Tin Monoxide Thin Films Deposited by Co-sputtering</b><br>Seungjun Lee, Eunsuk Hwang, Junshik Kim, Younjin Jang, and Cheol Seong Hwang<br><i>Department of Materials Science and Engineering and Inter-university Semiconductor Research Center, Seoul National University</i>   |
| TB2-D-5 | 11:40-11:55 | <b>Nonvolatile Memory Operations and Process Optimizations for the Memory Thin-Film Transistors using In-Ga-Zn-O Channel and Charge-Trap Layers</b><br>Da Jeong Yun, Han Byeol Kang, and Sung min Yoon<br><i>Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University</i>   |
| TB2-D-6 | 11:55-12:10 | <b>Effect of Film Density on Electrical Properties of Atomic Layer Deposited amorphous Zinc Tin Oxide Thin Film and TFTs</b><br>Jun Shik Kim, Eun Suk Hwang, Seungjun Lee, Younjin Jang and Cheol Seong Hwang   |

The 23<sup>rd</sup> Korean Conference on Semiconductors (KCS 2016)

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